1. Insulating Substrate
2. Ion Implanted Insulating Layer
3. Source Region / Drain Region
4. Channel Region
5. Gate Insulating Layer
6. Gate Electrode
7. Inter layer Insulating Layer
8. Source Electrode / Drain Region
9. Non-Single Crystal Silicon Layer
10. Resist Layer
11. Oxygen Ion Beam or Nitrogen Ion Beam
12. Impurity Ion Beam
13. Mask Insulating Layer

A: Source / Channel Boundary or Drain / channel Boundary

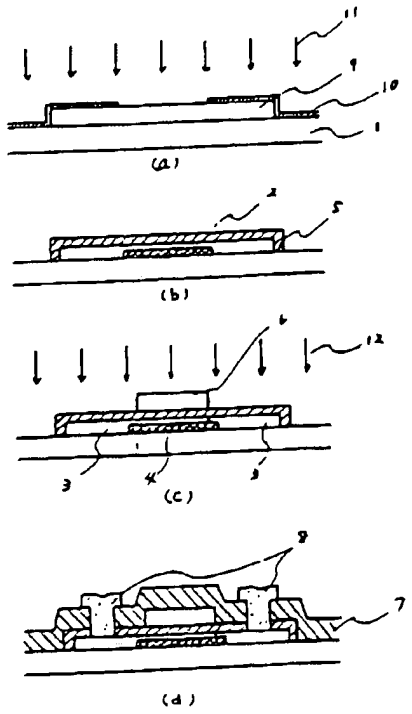

FIG. 3

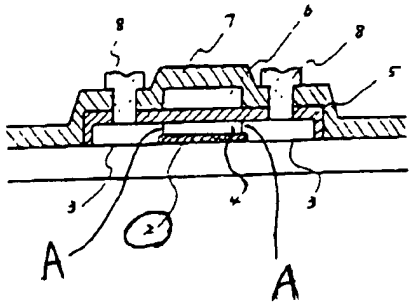

FIG. 1

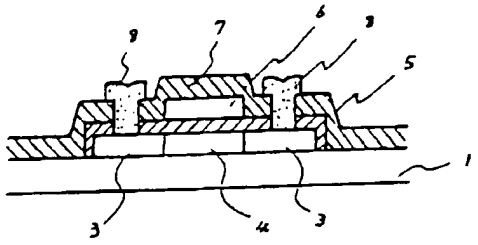

FIG. 2 (PRIOR ART)

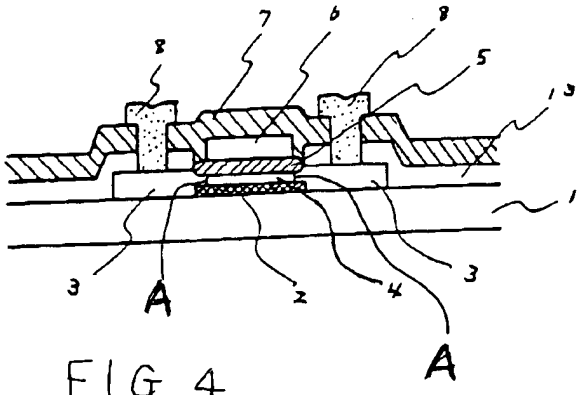

FIG. 4

Appendix I